

[0029] FIG. 7 is a cross-sectional view of a structure of a unit pixel of a stacked image sensor according to another exemplary embodiment.

DETAILED DESCRIPTION

[0030] Exemplary embodiments are described in greater detail below with reference to the accompanying drawings.

[0031] In the following description, like drawing reference numerals are used for like elements, even in different drawings. The matters defined in the description, such as detailed construction and elements, are provided to assist in a comprehensive understanding of the exemplary embodiments. However, it is apparent that the exemplary embodiments can be practiced without those specifically defined matters. Also, well-known functions or constructions are not described in detail since they would obscure the description with unnecessary detail.

[0032] It will be understood that when an element or layer is referred to as being “on” another element or layer, the element or layer may be directly on another element or layer or intervening elements or layers.

[0033] FIG. 1 is a plan view of a unit pixel of a stacked image sensor 100 according to an exemplary embodiment. FIG. 2 is a cross-sectional view taken along a line II-II' of FIG. 1.

[0034] Referring to FIG. 1, a pixel unit PU may include two green pixels G, a red pixel R, and a blue pixel B. FIG. 1 shows a Bayer pattern as an example, but the exemplary embodiment is not limited thereto. For example, the locations of the color pixels R, G, and B may be different from those shown in FIG. 1. Also, the pixel unit PU may include cyan, yellow, green, and magenta pixels. The stacked image sensor 100 may include a plurality of pixel units PU arranged in an array.

[0035] Referring to FIG. 2, the pixel unit PU may include a first photoelectric conversion layer 110. A second photoelectric conversion layer 130, a color filter layer 150, and a micro-lens layer 170 are sequentially stacked on the first photoelectric conversion layer 110.

[0036] The first photoelectric conversion layer 110 and the second photoelectric conversion layer 130 may be disposed in a silicon layer 140. The first photoelectric conversion layer 110 may include first photoelectric conversion regions 112 respectively disposed in the corresponding pixels. Each first photoelectric conversion region 112 may include a plurality of third photoelectric conversion regions 114. Each first photoelectric conversion region 112 may include two to four third photoelectric conversion regions 114. The first photoelectric conversion region 112 may include two third photoelectric conversion regions 114.

[0037] The second photoelectric conversion layer 130 may include one second photoelectric conversion region 132 at the corresponding pixel. The two third photoelectric conversion regions 114 and the second photoelectric conversion region 132 in one pixel may be doped regions. For example, the silicon layer 140 may be doped with a first type impurity, and the third photoelectric conversion regions 114 and the second photoelectric conversion region 132 may be regions doped with a second impurity. When the first impurity is an n-type impurity, the second type impurity may be a p-type impurity, and vice versa.

[0038] The second photoelectric conversion region 132 may be a general image detection region. The third photoelectric conversion regions 114 may perform auto-focusing

by detecting light passing through the second photoelectric conversion region 132 thereon. That is, the two third photoelectric conversion regions 114 in the pixel may perform phase detection auto-focusing (AF).

[0039] The third photoelectric conversion regions 114 may be also used as image detection regions.

[0040] The color filter layer 150 may include a plurality of color filters 150R, 150G, and 150B. In the red pixel R, the red color filter 150R is disposed on the second photoelectric conversion region 132 to selectively transmit red light. In the green pixel G, the green color filter 150G is disposed on the second photoelectric conversion region 132 to selectively transmit green light. In the blue pixel B, a blue color filter 150B is disposed on the second photoelectric conversion region 132 to selectively transmit blue light.

[0041] The micro-lens layer 170 may include a plurality of micro-lenses 172. The micro-lenses 172 are disposed on each of the color filters 150R, 150G, and 150B to collect incident light and to transmit collected light to the corresponding color filters 150R, 150G, and 150B.

[0042] The stacked image sensor 100 may include first barriers 181 that divide the pixels R, G, and B. The first barriers 181 may vertically pass through the first photoelectric conversion layer 110 and the second photoelectric conversion layer 130. The two third photoelectric conversion regions 114 and the second photoelectric conversion region 132 corresponding to the pixel may be disposed in a pixel region surrounded by the first barriers 181.

[0043] FIG. 3 is a cross-sectional view showing a structure of the first barrier 181 of FIG. 2. Referring to FIG. 3, each first barrier 181 may include a trench T that separates the pixels R, G, and B, an insulating layer 191 that covers an inner wall of the trench T, and a light absorption layer 192 that fills a hole formed by the insulating layer 191. The insulating layer 191 may be formed of thin silicon oxide. The light absorption layer 192 may be formed of, for example, polysilicon.

[0044] A second barrier 182 that separates the two third photoelectric conversion regions 114 in each of the pixels R, G, and B may be disposed in the first photoelectric conversion layer 110. The second barrier 182 may have the same structure as the first barriers 181 of FIG. 3, and the detailed description thereof will not be repeated.

[0045] The first barriers 181 and the second barrier 182 prevent incident light on a pixel from entering other adjacent pixel regions that causes a noise. That is, the insulating layer 191 reflects light that enters adjacent pixels after entering into a pixel, and light transmitted through the insulating layer 191 may be absorbed by the light absorption layer 192.

[0046] The stacked image sensor 100 may further include a signal processor that processes an electrical signal by receiving charges from the photoelectric conversion regions. The signal processor may include three to four transistors. The signal processor may be disposed below the first photoelectric conversion layer 110.

[0047] When visible light enters the stacked image sensor 100 from an image measuring object, red light of visible light passes through the red color filter 150R and generates charges in the second photoelectric conversion region 132. Based on the generated charges, the signal processor outputs an intensity signal of the red light. Green light and blue light of visible light enter the corresponding second photoelectric conversion region 132 respectively through the green color filter 150G and the blue color filter 150B and generate